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Standard Guide for Depth Profiling in Auger Electron Spectroscopy[1]

This standard is issued under the fixed designation E1127; the number immediately following the designation indicates the year of original adoption or, in the case of revision, the year of last revision. A number in parentheses indicates the year of last reapproval. A superscript epsilon (ε) indicates an editorial change since the last revision or reapproval.

1. Scope

1.1 This guide covers procedures used for depth profiling in Auger electron spectroscopy.

1.2 Guidelines are given for depth profiling by the following:

	Section
Ion Sputtering	6
Angle Lapping and Cross-Sectioning	7
Mechanical Cratering	8
Mesh Replica Method	9
Nondestructive Depth Profiling	10

1.3 The values stated in SI units are to be regarded as standard. No other units of measurement are included in this standard.

1.4 *This standard does not purport to address all of the safety problems, if any, associated with its use. It is the responsibility of the user of this standard to establish appropriate safety and health practices and determine the applicability of regulatory limitations prior to use.*

2. Referenced Documents

2.1 *ASTM Standards:*[2]

E673 Terminology Relating to Surface Analysis (Withdrawn 2012)[3]

E684 Practice for Approximate Determination of Current Density of Large-Diameter Ion Beams for Sputter Depth Profiling of Solid Surfaces (Withdrawn 2012)[3]

E827 Practice for Identifying Elements by the Peaks in Auger Electron Spectroscopy

E996 Practice for Reporting Data in Auger Electron Spectroscopy and X-ray Photoelectron Spectroscopy

E1078 Guide for Specimen Preparation and Mounting in Surface Analysis

E1577 Guide for Reporting of Ion Beam Parameters Used in Surface Analysis

E1634 Guide for Performing Sputter Crater Depth Measurements

E1636 Practice for Analytically Describing Depth-Profile and Linescan-Profile Data by an Extended Logistic Function

E1829 Guide for Handling Specimens Prior to Surface Analysis

2.2 *ISO Standard:*[4]

ISO/TR 22335: 2007 Surface Chemical Analysis—Depth Profiling—Measurement of Sputtering Rate: Mesh-Replica Method Using a Mechanical Stylus Profilometer

3. Terminology

3.1 *Definitions:*

3.1.1 For definitions of terms used in this guide, refer to Terminology E673.

4. Summary of Guide

4.1 In ion sputtering, the surface layers are removed by ion bombardment in conjunction with Auger analysis.

4.2 In angle lapping, the surface is lapped or polished at a small angle to improve the depth resolution as compared to a cross section.

4.3 In mechanical cratering, a spherical or cylindrical crater is created in the surface using a rotating ball or wheel. The sloping sides of the crater are used to improve the depth resolution as in angle lapping.

4.4 In nondestructive techniques, different methods of varying the electron information depth are involved.

5. Significance and Use

5.1 Auger electron spectroscopy yields information concerning the chemical and physical state of a solid surface in the near surface region. Nondestructive depth profiling is limited to this near surface region. Techniques for measuring the crater depths and film thicknesses are given in (**1**).[5]

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[1] This guide is under the jurisdiction of ASTM Committee E42 on Surface Analysisand is the direct responsibility of Subcommittee E42.03 on Auger Electron Spectroscopy and X-Ray Photoelectron Spectroscopy.

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[2] For referenced ASTM standards, visit the ASTM website, www.astm.org, or contact ASTM Customer Service at service@astm.org. For *Annual Book of ASTM Standards* volume information, refer to the standard's Document Summary page on the ASTM website.

[3] The last approved version of this historical standard is referenced on www.astm.org.

[4] Available from International Organization for Standardization (ISO), 1, ch. de la Voie-Creuse, CP 56, CH-1211 Geneva 20, Switzerland, http://www.iso.org.

[5] The boldface numbers in parentheses refer to a list of references at the end of this standard.

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5.2 Ion sputtering is primarily used for depths of less than the order of 1 µm.

5.3 Angle lapping or mechanical cratering is primarily used for depths greater than the order of 1 µm.

5.4 The choice of depth profiling methods for investigating an interface depends on surface roughness, interface roughness, and film thickness (**2**).

5.5 The depth profile interface widths can be measured using a logistic function which is described in Practice E1636.

6. Ion Sputtering

6.1 The specimen should be handled in accordance with Guides E1078 and E1829. First introduce the specimen into a vacuum chamber equipped with an Auger analyzer and an ion sputtering gun. Align the ion beam using a sputtering target or a Faraday cup, paying careful attention to the relative spot size of the electron beam, ion beam, and Faraday cup and their respective orientations to ensure accurate convergence of the two beams at the specimen surface.

6.1.1 Place the specimen in front of the Auger analyzer and direct the ion gun towards the analysis area. If the ion beam is not normal to the specimen surface then possible shadowing of the analysis area from the ion beam, due to surface roughness, must be considered. The ion beam conditions should be reported in accordance with Guide E1577.

6.2 Choose the elements to be investigated from previous experience or from an initial Auger electron spectrum or an energy-dispersive X-ray spectrum since the latter spectrum can reveal additional elements present at depths greater than those that contribute to the Auger electron spectrum (**3**). Select a specific transition for each element. During the depth profiling, record the peak-to-peak heights for Auger derivative data, or peak heights or peak areas for *N(E)* data. The data may be gathered during continuous sputtering or between timed sputter segments. Results may vary between the two techniques.

6.2.1 One source of their difference is due to the presence of ion-induced electrons during continuous sputter depth profiling, especially at low-electron kinetic energies, that can become comparable in intensity to the electrons induced by the probing incident electron beam. Unless one or the other of the excitation beams is modulated and detected synchronously these two types of emitted electrons are difficult to distinguish. These ion-induced electrons usually form a featureless background that rises steeply as their kinetic energy decreases, but sometimes ion-induced Auger peaks might be present whose lineshape may be different from those produced by the electron beam (**4**). As a result, care must be taken during continuous sputtering to ensure reliable results. Another source of difference is due to the buildup of adsorbed species during the data acquisition time in the discontinuous sputter depth profile mode (**5**). If portions of the ion-eroded surface expose very reactive phases, then Auger peaks due to adsorbed species, for example, oxygen or carbon, or both, will appear in the spectra and mask the actual depth distribution.

6.2.2 It is advisable when analyzing an unknown specimen to periodically examine survey scans to detect any new elements that were not present in the initial survey scan and to determine if any of the Auger peaks have been displaced outside of their analysis windows (**6**).

6.3 Crater-edge profiling of the sputter-formed crater by using Auger line scans is a technique similar to the analysis of the mechanically formed craters in Section 8 (**7**). Forming the crater by sputtering may introduce the additional complications of ion-induced damage and asymmetric crater dimensions.

6.4 If specimen rotation is used to reduce ion-induced roughness, then the rotational speed, rotation axis runout relative to ion beam sputtered area or wobble and data acquisition rate should be reported (**8**, **9**).

6.5 Identify the elements in the survey scans using Practice E827.

6.6 The Auger data and the sputtering conditions should be reported as described in Practice E996.

6.7 There is extensive information available in the literature on the effects of ion bombardment on solid surfaces (**10-15**).

6.8 Special care must be exercised whenever specimen temperature changes are present because effects due to surface diffusion, surface segregation or diffusion limited bulk processes such as point defect migration can occur and dramatically alter the specimen composition, even over depths larger than the ion beam penetration depth which is typically a few nanometers (**16**, **17**). The concept of preferential sputtering in multielement, single-phase specimens has altered significantly so that chemical effects such as surface segregation are considered to be at least as important as physical effects such as mass differences in the evolution of the near surface composition during sputter depth profiling (**18-21**). Since the probing depths in Auger electron spectroscopy are usually smaller than the ion-penetration depth these effects are very important in any interpretation of Auger signal intensity in terms of composition during ion-beam profiling. Computer modelling of these and other ion-induced phenomena has been extensively studied and has provided new insights into this field (**22**, **23**).

6.8.1 It should be determined for each specimen if compositional changes or other sputter effects are likely to occur. It may be possible to minimize these effects in some instances by adjusting the sputtering parameters.

6.9 Ion guns used in Auger analysis are normally self-contained units capable of producing a focused beam of ions. The specimen is not used as an anode for the gun. Many ion guns are able to raster the ion beam. A rastered ion beam will produce a more uniform ion current distribution on the specimen surface in the region of analysis.

6.10 If the ion gun is differentially pumped, the vacuum pumps may be left on during sputtering, removing most of the sputtered gases. If not, then the chamber must be back filled with gas and provisions for removing the sputtered active gases must be considered. Titanium sublimation is effective in removing these gases.

6.11 Noble gas ions are normally used in sputtering and the most commonly used gas is argon. Xenon is occasionally used